



SHEET 1 OF 1

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
055071-0329SERIAL NO.
10/756,830APPLICANT
Doug van den BROEKE, et al.FILING DATE
January 14, 2004GROUP
2891

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
CME		US 5,895,741	04-20-1999	Hasegawa et al.	
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						Yes	No
CME		EP 1 202 119 A1	05-02-2002	ASML Masktools B.V.		x	
CME		WO 03/054626 A1	07-03-2003	ADVANCED MICRO DEVICES, INC.		x	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
CME		Christoph DOLAINSKY, et al., "Simulation based method for sidelobe suppression," Optical Microlithography XIII, Proceedings of SPIE, 2000, pp 1156-1162, Vol. 4000
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		Nicolas Bailey COBB, "Fast Optical and Process Proximity Correction Algorithms for Integrated Circuit Manufacturing," Ph.D. dissertation, Spring 1998, pp 35-72, University of California at Berkeley
		J. Fung CHEN, et al., "Practical I-Line OPC Contact Masks for Sub-0.3Micron Design Rule Application: Part 1—OPC Design Optimization," pp 181-201
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C. Juerkett

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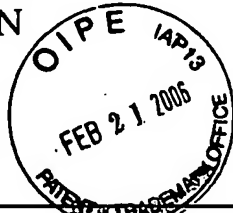
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1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.

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<i>CME</i>		US 5,229,230	07/20/1993	Kamon	
<i>CME</i>		US 5,895,741	04/20/1999	Hasegawa et al.	
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<i>CME</i>		WO 02/03140 A1	01/10/2002	NUMERICAL TECHNOLOGIES, INC.		X
<i>CME</i>		EP 1 237 046 A2	09/04/2002	ASML MASKTOOLS B.V.		X

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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C. J. P. J. J.

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